

STM/STS STUDIES OF 2D MATERIALS

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New Frontiers in 2D materials: Approaches & Applications, Villard de Lans, January 2017

Introduction:

Scanning Tunneling Microscopy (STM) and Spectroscopy (STS)

WSXMsoftware, Nanotec, Spain

 Heinrich Rohrer & Gerd Binnig, IBM Zürich (1982)

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Introduction to Scanning Tunneling Microscopy (STM)

 \bullet **Principle of constant current imaging**.

Introduction to Scanning Tunneling Microscopy (STM)

•**Role of the electronic structure.**

Tersoff-Hamann theory (PRL 50, 1988 (1983)).

Full 3D theory: spherical tip (radius R).

At **low bias** (V) and **low temperature**, the tunneling current is given by:

$$
I \approx \frac{e^2 V}{h} \beta e^{2kR} \rho_s(\vec{r}, E_f) \rho_t(E_f)
$$
 $\beta = \frac{2\pi}{h}$

$$
3 = \frac{2\pi \frac{3}{h} \frac{4}{h} R^2}{m^2}
$$

 $\rho_{_S}(\vec{r},E_f)$: LDOS of the sample at E_f , evaluated at the **center** of the tip. $\rho_t(E_f)$: DOS of the tip at E_f .

Both the topography and the spatial variations of the LDOS of the sample contribute to the current.

Introduction to Scanning Tunneling Microscopy (STM)

•**Voltage dependent imaging: electronic effects.**

Empty states : **V=1V**

Occupied states : **V=-1 V**

γ (mixed) phase of Pb/Si(111) (R3 type) **Same area**. Size : 30x30 nm^²

Gòmez-Rodrìguez et al, Surf. Sci. 377**,** 45 (1997)

Model of **Tersoff & Hamann (PRL 1983)**, extended by Lang (PRB 1986) Sample bias: *V*tip-surface distance: s *T*=0*K*, $N_T(E)$ =Cste...

$$
I(r,V)=\frac{e\beta}{\hbar}N_T(E_F)e^{-2\kappa s}\int_{E_F}^{E_F+eV}\rho_S(r_{//},E)dE
$$

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Model of **Tersoff & Hamann (PRL 1983)**, extended by Lang (PRB 1986) Sample bias: *V*tip-surface distance: s *T*=0*K*, $N_{\tau}(E)$ =Cste...

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Model of Tersoff & Hamann (PRL 1983) extended by Lang (PRB86) Sample bias: *V*tip-surface distance: s *T(E)=Cste…*

Constant current STM mode: map of ∆**^ztip(x,y)** with ^a**current feedbackloop activated**

Topography

Model of Tersoff & Hamann (PRL 1983) extended by Lang (PRB86) Sample bias: *V*tip-surface distance: s *T(E)=Cste…*

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Model of Tersoff & Hamann (PRL 1983) extended by Lang (PRB86) Sample bias: *V* tip-surface distance: *^s T=0K, NT(E)=Cste…*

$$
I(r, V) = \frac{e\beta}{\hbar} N_T (E_F) e^{-2\kappa s} \underbrace{\int_{E_F}^{E_F + eV} \rho_s(r_{//}, E) dE}_{\text{Surface Local Density of States (LDOS)}}
$$

Accounts for the decay of the sample eigenstates into vacuum. E and k// dependence?

 $E_{\rm vac}$

Wavefunction matching at the sample-vacuum interface: E and k// are conserved for a given state.

κ can be obtained from I(z) spectroscopy: open feedback loop,ramp « ^s » by tens of pm and measureI (at given V).

For the simple **« step potential » model** of the interface. ${\rm Schr\ddot{o}}$ dinger equation in vacuum <mark>for a state at E_F:</mark>

$$
\Phi = \frac{\hbar^2}{2m} \left(\kappa^2 - k_{//}^2 \right)
$$
 thus $\kappa = \sqrt{0.262 \Phi + k_{//}^2}$

^κ and *^k*// in Å-1, ϕ in eV. Typically: ϕ≈4 eV.

-
- For k_{//}=0 Å⁻¹ (Γ point): κ≈1 Å⁻¹
• For k_{//}=1.7 Å⁻¹ (K point in Gr): κ≈2 Å⁻¹

Since s≈5Å, the tunneling current is more sensitive to the states with small wavevectors.

Introduction to Scanning Tunneling Spectroscopy (STS)

•**Principle: I(V) curves at constant tip-sample separation (feedback off).**

Vs=0 V. I=0

^Vs>0 V. e flow fromtip to sample. **Empty states.**

Sample

(d)**Occupied states ^Vs<0 V.** e flow fromsample to tip.

For a **structureless tip DOS**, at low bias and temperature:

$$
\left|\frac{dI}{dV}\propto\rho_{s}(\vec{r},E_F+eV)\right|
$$

Spectroscopy⇔ **LDOS of the sample** N. D. Lang, PRB 34, 5947 (1986)

Asymmetry between occupiedand empty states.

Other normalisation (high bias):

$$
\rho_s(eV) \propto \frac{V}{I} \frac{dI}{dV}
$$

R. M. Feenstra et al. Surf. Sci. 181, 295 (87).

Tip

Scanning Tunneling Spectroscopy (STS)

Dynamical Tunneling Conductance at Zero temperature:

$$
\left. \frac{dI}{dV(\vec{r},V)} \sim \rho_S(\vec{r},E_F+eV) \right|
$$

$$
|V|<1V
$$

Scanning Tunneling Spectroscopy (STS)

Dynamical Tunneling Conductance at Zero temperature:

$$
dI/dV(\vec{r},V) \sim \rho_S(\vec{r},E_F+eV)
$$

$$
|V|<1V
$$

At finite temperature:

$$
dI/dV(\vec{r},V) \sim \int_{-\infty}^{\infty} dE \frac{df(E-eV,T)}{dE} \rho_S(\vec{r},E)
$$

Quantity roughly proportional to **ρS(r,E^F+eV)**, with a thermal broadening of 3.52 ${\sf k}_{\sf B} {\sf T}$

Need for cryogenic STM/STS

 \rightarrow Spectroscopic resolution: \sim 1meV à 4,2K

Graphene & Co. : Frontier Research in Graphene-based Systems, April 2014

Scanning Tunneling Spectroscopy (STS)

Dynamical Tunneling Conductance at Zero temperature:

 $dI/dV(\vec{r}, V) \sim \rho_S(\vec{r}, E_F + eV)$ $|V| < 1V$

2 modes of spectroscopic imaging:

« CITS » mode: spectra taken at each point of a constant current image @ (V_{set}, I_{set})

- Time consuming but complete set of data.
- Ultimately atomic resolution spectroscopy can be achieved.

Conductance image ω (V_{set} , I_{set}) with small ac (ω) bias added to dc bias.

- Closed loop image: faster, but only one sample bias/image …
- ^ω between the cut-off frequencies of feedback loop and current PA.
- Allows for fast identification of changes in electronic structure at large scale.

In both cases some **cross-talk with « topographic »** features @ (V_{set} , I_{set}) may occur. Change V_{set}...

A few STM setups in several environments…

P. Mallet, D. Défourneau, D. Roditchev

P. Mallet, J.Y. Veuillen, M. Pissard

VT UHV STM 40K-300KLEPES 1999

R. Cinti, P. Mallet, P. Chevalier, J.Y. Veuillen P. Mallet, J.Y. Veuillen, J.F. Motte

Graphene & Co. : Frontier Research in Graphene-based Systems, April 2014

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Implementation of our setups in the Nanoscience building @ NEEL Institute

VT-UHV-STM and LT-UHV-STM (march 2013 - …)

Experiments on concrete foundations (mass 500 tons)

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LT-STM head (here without thermal screens)

STM on 2D conductive systems at surfaces

- \checkmark STM is a nice tool to study their electronic structure at atomic scale
- **UHV environment is required** to preserve most of the 2D systems
- \checkmark Complementary techniques are most of time necessary, for instance ARPES for the band structure of the occupied states, and ab initio calculation
- \checkmark STM tells a lot regarding the morphology of the disorder existing in the system, and its direct impact on the 2D properties
- \checkmark More importantly, disorder can be tuned exposing the 2D system to ionic bombardment, deposition of any metals, exposition to a gas…

STM/STS of graphene and graphene-based nanostructures

Outline: graphene

- I. Atomic resolution
- II. Interface contribution to graphene STM images
- III. Local spectroscopy and spatial variations of the Dirac point
- IV. Dirac Quasiparticle Interferences
- V. STM/STS under magnetic field
- VI. Point defects
- VII. Moiré ingeneering of graphene's band structure

•Mostly on G/SiC, G/SiO2, G/BN (HOPG and G/HOPG)

Synthesis of graphene on SiC in UHV @ NEEL

(A technique introduced by van Bommel in… 1975!)

■ We use commercial wafers of hexagonal 6H-SiC n-doped or semi-insulating

Either SiC (0001) or SiC(000-1) are studied (resp. Si- and C- terminated)

Graphitization occurs **using thermal decomposition in UHV (some other groups use non UHV conditions, Ar pressure…)**

Synthesis of graphene on SiC in UHV (NEEL Institute)

- ✓ **UHV preparation chamber equiped for standard surface science (ebeam anneling, LEED and Auger electron spectroscopy)**
- ✓ **SiO² removal under Si flux @ 850**°**^C**
- ✓**Progressive annealing** (900° C \rightarrow 1200° C), graphitization process **controlled by LEED and Auger spectroscopy**

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UHV-grown graphene samples in the ML range

Low Energy Electron Diffraction patterns

C face: rotational disorder

Difference in the structure of graphene layers grown on:

6H-SiC(0001) (Si face) 6H-SiC(000-1) (C face)

Known from van Bommel et al., Surf. Sci. 1975

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Part I. Atomic resolution on graphene STM images

ML graphene on SiC(0001) P. Mallet/J.Y. Veuillen, Institut NEEL CNRS/UJF, Grenoble

Electronic structure of pristine graphene

Graphene is a single carbon plane arranged on a honeycomb lattice

```
► two sublattices (A and B atoms)<br>► d = 1,419 Å
\geq d_{A-B} = 1,418 \text{ Å} a=b=2,456 Å
```
Graphene is a gapless semiconductor:

 Linear and isotropic band structure around K and K' points

> Trigonal warping for|E|>0.5eV

Electronic structure of pristine graphene

Linear and isotropic dispersion at K et K' valleys: **Dirac Cones Massless Dirac Quasiparticles** π and π^* bands

Band structure: ML versus BL

Monolayer

 $\Psi^{\bf k}({\bf r})=c_A({\bf k})\Phi^{\bf k}_A({\bf r})+c_B({\bf k})\Phi^{\bf k}_B({\bf r})$ $|c_A({\bf k})| = |c_B({\bf k})|$

Band structure: ML versus BL

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PHYSICAL REVIEW B 76, 041403(R) (2007)

Electron states of mono- and bilayer graphene on SiC probed by scanning-tunneling microscopy

P. Mallet,¹ F. Varchon,¹ C. Naud,¹ L. Magaud,¹ C. Berger,^{1,2} and J.-Y. Veuillen¹ ¹Institut Néel, CNRS-Université Joseph Fourier, Boîte Postale 166, F-38042 Grenoble Cedex 9, France ²Georgia Institute of Technology, Atlanta, Georgia 30332-0430, USA

ML and BL Graphene on SiC – Si face

STM in UHV @ 40K

On the SiC - Si face, a carbon buffer layer exists at the interface, strongly bond to the SiC substrate

Buffer layer: Complex interface reconstruction: SiC-6√3x6√3 R30°

Apparent distorsion of period ≈ 1.9 nm

Total charge density map (DFT calculation)F. Varchon, P. Mallet, J.Y. Veuillen and L. Magaud, PRB'08

PHYSICAL REVIEW B 76, 041403(R) (2007)

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Sample Bias: 200 mV. Size: 4 x 4 nm²

See also Brar et al., APL 2007

STM measurements at low bias:**ML:** Same LDOS on A and B sublattices
BL: Strong LDOS asymmetry between A **BL: Strong LDOS asymmetry between A and B atoms**

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Structural and electronic properties of bilayer epitaxial graphene

G.M. Rutter, J.N. Crain, N.P. Guisinger, P.N. First and J.A. Stroscio, JVST 26, 938 (2008)STM in UHV @ 5K

BL graphene:

At sample bias higher than 0.4 eV (interlayer hoping energy): **honeycomb-like atomic patternsame LDOS on A and B surface sublattices**

Part II. Interface contributionto the STM images

(non metallic substrates)

Scanning tunnelling microscopy and spectroscopy of ultra-flat graphene on hexagonal boron nitride

Jiamin Xue¹, Javier Sanchez-Yamagishi², Danny Bulmash², Philippe Jacquod^{1,3}, Aparna Deshpande^{1†}, K. Watanabe⁴, T. Taniguchi⁴, Pablo Jarillo-Herrero² and Brian J. LeRov^{1*}

NATURE MATERIALS | VOL 10 | APRIL 2011

a

d

Frequency (arb. units)

Local Electronic Properties of Graphene on a BN Substrate via **Scanning Tunneling Microscopy**

Régis Decker, ****, \$ Yang Wang, *; \$ Victor W. Brar, *; * William Regan, * Hsin-Zon Tsai, * Qiong Wu, * William Gannett, ** Alex Zettl, *; * and Michael F. Crommie *; *

Nano Lett. 2011, 11, 2291-2295

Graphene on h-BN/SiO2/Si++ , STM fir **+ Au electrode** STM in UHV @ 5K $50 \mu m$ SiO. G/BNh Doped S ene / BN / SiO₂ Z_{max} Graphene / BN 0.21 Au \overline{a} \mathbf{a} Graphene Height (pm) Sio h-BN v: 100 nm $x:100$ nm G/SiO2c $1.0₊$ z_{max} G/SiO2topography 0.94 -670 10_{nm} ПL 0.5 « Flat »G/BN $x:100 \text{ nm}$ $v: 100$ nm $-700 - 350$ 350 700 $\overline{0}$ Large corrugation for $G/SiO2$: (\approx 1 nm) Height (pm) Weak Z corrugation on G/h-BN: (10 to 100 pm) NB same order of magnitude on G on SiC

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 « Rippled » **Local curvature**

Graphene / SiO,

raphene / SiO.

 10_{nm}

Morphology of UHV-grown Graphene on SiC – Si face STM @ 40K

BL

Constant current image

200x126 nm², sample bias: -1V

■ Rough terraces (**ML)** → graphene ML
Annarent roughness related to the interf **Apparent roughness related to the interface**

- Smooth terraces (**BL)** → mostly graphene BL
- **■ No abrupt step edges: "carpet" like behaviour** (cf insert)

Mallet et al., PRB 76, 041403(R) (07)

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BL B

graphene

BL

ML

BL

BL

ML

Graphene ML and BL on SiC(0001)Interface states

Saturation of contrast

L58, 25x25 nm², -0.1V, 0.1nA.

•Low bias image: **-100mV**. •**M**: monolayer, **B**: bilayer.•Same orientation for M and B.

•**"Interface" states probed below Monolayer.**•**No such effect on Bilayer.**(id. **Riedl et al**., PRB **76**, 245406 (07)**Lauffer et al**., **Rutter et al**.)

•**Spots in the red are related to the SiC-6√3x6√3 R30**° **interface reconstruction Varchon et al**, PRB 77, 235412 (08) TE: 12.2x12.2 1/nm²

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STM "Transparency" of ML graphene at high sample bias

Graphene on SiC – Si face

Iset=1.0nA, 8x8 nm².

This transparency results from High tunneling probabilities into the available interface states: - Large Interface LDOS at high bias (compared to graphene LDOS)

- Hindered tunneling into graphene states (due to their large k// component)

$$
\left|\Psi_{\vec{k}}(x,y,z)\right|^2 \propto e^{-2\widetilde{\kappa}z} \qquad \qquad \kappa = \sqrt{\left|\overrightarrow{\Gamma\Kappa} + \overrightarrow{q}\right|^2 + \frac{2m\Phi}{\hbar^2}}
$$

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STM "Transparency" of ML graphene at high sample bias

Graphene on SiC – Si face

Iset=1.0nA, 8x8 nm².

This transparency allows a direct study of the real interface structure (here the buffer layer), which is far from perfectly ordered !

More generally: allows for a study of the changes induced by Gr in the susbtrate atomic orelectronic structure:

Gr on SiC-C face: F. Hiebel et al., PRB 86, 205421 (2012)
WW.neet.cnrs.fr **Gr on Me:** Ir(111): S. J. Altenburg et al., PRL 108, 206805 (2012), Cu(111): H. Gonzalez Herrero et al. , ACS Nano 10, 5131 (2016)
PHYSICAL REVIEW B 76, 235416 (2007)

Imaging the interface of epitaxial graphene with silicon carbide via scanning tunneling microscopy

G. M. Rutter,¹ N. P. Guisinger,² J. N. Crain,² E. A. A. Jarvis,² M. D. Stiles,² T. Li,¹ P. N. First,^{1,*} and J. A. Stroscio^{2,*} ¹School of Physics, Georgia Institute of Technology, Atlanta, Georgia 30332, USA ²Center for Nanoscale Science and Technology, NIST, Gaithersburg, Maryland 20899, USA

From empty-state images, STM revelas two predominant adatom structures: pyramidal clusters and hexagonal rings.

- 1. Si adatoms arrange in pyramidal clusters tetramers (red arrow). The top atom is transparent in filled states.
- 2. Hexagonal rings of Si adatoms

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Part III.Local spectroscopy, Dirac point mapping

$$
dI/dV(V)\sim -\int_{-\infty}^{\infty}dE\frac{df(E-eV,T)}{dE}\rho_{S}(\mathbf{r},E)
$$

 \rightarrow Thermal broadening \sim 1meV à 4,2K

Graphene on SiC – Si face STM in UHV @ 5K (except in Lauffer @ 77K)

- •Gap-like structure around E_F, **but not systematic** (Rutter PRB), width 100 – 130 meV
- •Clear dip in occupied states (-0.3 ; -0.35 eV) for BL
- •For ML ???

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- •Thus for ML graphene on SiC(0001), a dip at -0.45 V is expected in dl/dV(V)
- • However, it is hardly detectable by STS, due to the large contribution of the interface states

•For BL graphene on SiC(0001), the dip ω -0.35 eV is indeed the Dirac point (No spurious contribution of interface states)

Possible origin for the zero bias gap

Giant phonon-induced conductance in scanning tunnelling spectroscopy of gate-tunable graphene

YUANBO ZHANG^{*}, VICTOR W. BRAR^{1,2}, FENG WANG^{*}, CAGLAR GIRIT^{1,2}, YOSSI YAYON^{*}, MELISSA PANLASIGUI¹, ALEX ZETTL^{1,2} AND MICHAEL F. CROMMIE^{1,2*}

1Department of Physics, University of California at Berkeley, Berkeley, California 94720, USA ² Materials Sciences Division, Lawrence Berkeley Laboratory, Berkeley, California 94720, USA "e-mail: zhvb@berkelev.edu: crommie@berkelev.edu

Nature Physics 4, 627 (2008)

GATED Graphene on SiO2/Si++

Au electrodes contact the Graphene flakes STM in UHV @ 5K

VD is gate voltage dependant, not the zero bias gap (width 130mV) Origin of the zero bias gap?

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A mechanism based on Inelastic Tunneling

Above the energy threshold at 65 meV: **an inelastic tunneling chanel is activated,** giving rise **to a strong conductance increase.**

Possible coupling with the **67 meV out-of plane acoustic phonon modes located near the K/K' points**.

Mohr et al., PRB 76, 035439 (2007)

Zhang et al., Nature Physics 4, 627 (2008) Wehling e tal., PRL 101, 216803 (2008)

Graphene& Co. : Frontier Research in Graphene-based Systems, April 2014

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Possible coupling with the **67 meV out-of plane acoustic phonon modes located near the K/K' points**.

 0.5

Decay length (Å)

 $\overline{2}$

 $\overline{3}$

 $Z(\AA)$

0.08

0.06 \P^2

0.04

0.02

 $0₀$

Graphene state

State of FEG at ^Γ (at +3.3eV)

 $\overline{\mathbf{A}}$

Such phonon modes **mix** the nearly free-electron bands at ^Γ with the Dirac-like π bands at K (virtual transitions between 2D electronic bands)

The strong conductance enhancement results from the muc hslower decay of states at ^Γ into the vacuum.

 $\bf{0}$

Sample bias (V)

 $-0.2 -0.1$

 0.1

 0.2

$$
z, k_{\parallel}) \propto e^{-z/\lambda}, \qquad \lambda^{-1} = 2\sqrt{2m\phi/\hbar^2 + k_{\parallel}^2}
$$

Zhang et al., Nature Physics 4, 627 (2008) Wehling et al., PRL 101, 216803 (2008)

NB: no such « gap-like » feature on point defects (Nsub) due to local symmetry breaking (J. Lagoute et al., PRB 91, 125442 (2015))

 $\overline{5}$

Mohr et al., PRB 76, 035439 (2007)

Charge puddles

Yuanbo Zhang^{1*†}, Victor W. Brar^{1,2*}, Caglar Girit^{1,2}, Alex Zettl^{1,2} and Michael F. Crommie^{1,2†} Nature Physics 5, 722 (2009)

Graphene on SiO2/Si++ STM in UHV @ 5K

Yuanbo Zhang^{1*†}, Victor W. Brar^{1,2*}, Caglar Girit^{1,2}, Alex Zettl^{1,2} and Michael F. Crommie^{1,2†} Nature Physics 5, 722 (2009)

Graphene on SiO2/Si++ STM in UHV @ 5K

\rightarrow Charge puddles

Graphene & Co. : Frontier Research in Graphene-based Systems, April 2014

Yuanbo Zhang^{1*†}, Victor W. Brar^{1,2*}, Caglar Girit^{1,2}, Alex Zettl^{1,2} and Michael F. Crommie^{1,2†} Nature Physics 5, 722 (2009)

Spatial variation of E_{D,} revealing charge puddles an order of magnitude larger than the size of topographic corrugationsOrigin: individual charge impurities located beneath the graphene sheet(from high bias dI/dV maps)

> *See also Deshpande et al., PRB 2009Graphene & Co. : Frontier Research in Graphene-based Systems, April 2014*

Yuanbo Zhang^{1*†}, Victor W. Brar^{1,2*}, Caglar Girit^{1,2}, Alex Zettl^{1,2} and Michael F. Crommie^{1,2†}

Topo

Same region 60x60nm² for all images.

 dI/dV just below DP **Curvature For puddles**

 0.2

09

No relationship between topo or curvature and puddles (<puddle size>: 20 nm)

Scattering centers (dots in dI/dV maps).

dI/dV well above (>0.45eV) the DP identifying the **charged impurities as scattering centers**

Dependence of the puddles on the carrier density.

for increasing gate voltages. <Neutral point> is for **Vg≈38 V**.

- \bullet • Amplitude and size of the fluctuations (puddles) increases as the DP approaches E_F
- Due to **increased** (decreased) **screening** by the Gr carriers as their density **n** increases \bullet (decreases): qTF*α*qF *α* √n for Gr *(qTF: Thomas Fermi sreening vector).*
- Experimental: <Puddle size> α 1/q_{TF} α 1/Vn \bullet
- \bullet *Well described by self consistent theory based on RPA.*

Scanning tunnelling microscopy and spectroscopy of ultra-flat graphene on hexagonal boron nitride

Jiamin Xue¹, Javier Sanchez-Yamagishi², Danny Bulmash², Philippe Jacquod¹³, Aparna Deshpande¹¹, K. Watanabe⁴, T. Taniguchi⁴, Pablo Jarillo-Herrero² and Brian J. LeRoy^{1*}

Nature Materials 10, 282 (2011)

G/h-BN versus G/SiO2STM in UHV @ 5K (at fixed gate voltage)

G/h-BN versus G/SiO2:Electron–hole charge puddles are reduced by two orders of magnitude (for charge).

Local Electronic Properties of Graphene on a BN Substrate via **Scanning Tunneling Microscopy**

Régis Decker, *.*:4,5 Yang Wang, *.5 Victor W. Brar, *.* William Regan, * Hsin-Zon Tsai, * Qiong Wu, * William Gannett, *.* Alex Zettl, *.* and Michael F. Crommie^{+,+}

'Department of Physics, University of California Berkeley, Berkeley, California 94720, United States ⁴Materials Science Division, Lawrence Berkeley National Laboratory, Berkeley, California 94720, United States

Nano. Lett. 11, 2291(2011)

G/h-BN versus G/SiO2

STM in UHV @ 5K, with backgate voltage V_G

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 V_{G} **= 15V**

Part VI. Point defects

Point defects on graphene

- \bullet Defects are supposed to degrade the transport properties of graphene, but canalso be exploited for Gr functionnalization.
- \bullet A number of possible cases: adsorbates, substitutional, vacancies…. for various purposes: doping, creating local moments, inducing « topological » phases….
- • A « classical » case: the C « vacancy » . *Magnetism in graphitic systems.*
- \bullet H on Graphene: local magnetic moments.
- \bullet Other defects: divacancies, substitutionnal N.

Early STM study: single vacancies on graphite

A very **localized defect** (atomic size) induces a **spatially extended**(a few nm) **perturbation**!

STM

K.F. Kelly, N.J. Halas / Surface Science 416 (1998) L1085-L1089 H.A. Mizes, J.S. Foster, Science 244 (1989) 559

Plenty of calculation, cf DFT H. Amara, S. Latil, V. Meunier, P. Lambin, and J. C. Charlier Phys. Rev. B76 115423 (2007).

C « vacancy » in graphene

*A simple model***:**

- •• Graphene as a « honeycomb » lattice of p_z orbitals with only NN TB coupling.
- •• A « vacancy » is just a missing p_z orbital on one sublattice (A or B).

The « vacancy » in sublattice A generates a « zero energy mode » at the Dirac point, which exits only on sublattice B and which is « semilocalized » (WF decays as $1/r$).

First non zero energy state: delocalized

Zero energy state: (semi) localized

V. M. Peirera et al., PRB 77, 115109 (2008),

see also:

B. R. K. Nanda et al., NJP 14, 083004 (20012), M. Inui et al., PRB 49, 3190 (1994)

C « vacancy » in graphene

A simple model (continued):

 \bullet As a result of electron-electron interaction (exchange energy gain), this « zero energy mode » should undergo spin polarization.

O. V. Yazyev, Rep. Prog. Phys. 73, 056501 (2010) for a **review.**

•**•** Emergence of a local magnetic moment with spin S=1/2 (m=1 μ_B). In agreement with Lieb's theorem (E. H. Lieb, PRL 62, 1201 (1989))

Spin density around a « vacancy »Spins up and down H. Kumazaki et al., JPSJ 76, 064713 (2007)

Spin splitting of the « zero energy mode » from a model Hubbard model (local **e-e interaction**).J. J. Palacios et al., PRB 77, 195428 (2008)

The « magnetic » state shouldshow up in STS measurements

 (2 peaks straddling the Dirac point even in non SP measurements).

Experimental realization?

Possible realizations of a C « vacancy » in graphene

Existence of magnetic moments in graphene from **non local** measurements: K. M. McCreary et al., PRL 109, 186604 (2012) (H_G, transport); X. Hong et al., PRL 108, 226602 (2012) (F_G, transport); R. R. Nair et al., Nat. Phys. 8, 199 (2012) and Nat. Commun. 4, 2010 (2013) (Vacanciesand adsorbates, SQUID magnetometry+doping).

H adsorbate on Gr from DFT calculations

Structure of an H adsorbate from DFT J. O. Sofo, PRB 85, 115405 (2012)D. W. Boukhvalov et al., PRB 77, 035427 (2008)

« sp3-like » configuration fo the C atombonded with H.

Adsorbtion energy for the H atom ≈ 1 eVfrom DFT.

Magnetic moment: 1 $\mu_{\rm B}$ **/unit cell.**

M. Moaied et al., PRB 90, 115441 (2014) and references therein.

Band structure and DOS for an H adsorbate on graphene: **non SP** DFT calculation. F. Yndurain, PRB 90, 245420 (2014)

Structure and spin density of an H adsorbate on ML Gr from **SP DFT**. M. Moaied et al., PRB 90, 115441 (2014)

Overview: 0.4V, 30pA, 28 x 28 nm²

H atoms on differentsublattices

0.4V, 30pA 8.8 x5.5 nm $^2\,$

Spatial extension of the spin-polarized electronic state induced by H atoms in undoped graphene.

On **neutral** (intrinsic) **graphene**.

H adsorbate on Gr: dimers

 Sublattice dependence of the magnetic coupling between neighboring H atoms.

Same sublattice => peak is polarized Different sublattices => no peaks

As expected from Lieb's theorem for AA dimers and from the coupling of "vacancy" states for AB dimers (J. J. Palacios et al., PRB 77, 195428 (2008))

Substitutionnal N atoms in Gr: doping and defect state.

- • Substitutional N expected to be an n-type dopant (e donor) to graphene with minimal structural perturbations.
- •N incorporation: direct growth (e. g. CVD with $NH₃$) or post-treatment of pristine Gr (N radicals here).

Results: identification of N induced species (STM), **e-doping** (shift of the Dirac point in STS), **localized resonance** (donor state) induced by **N subst**.

Divacancies on Gr

- •« True » divacancies produced by mild ion bombardment (Ar⁺, 140eV) and annealing (650°C).
- •Observed on different realizations of « graphitic » samples (HOPG, ML and BL on SiC-Si, FLG on SiC-C).

• Twofold symmetric features « ^A » and « ^B » (not single vacancies: 3 fold).

• Divacancies are much more stable than2 isolated ones (by ≈8 eV) from DFT. Gun-Do Lee eet al., PRL 95, 205501 (2005)

26x26 nm², +0.28V

M. M. Ugeda et al., PRB 85, 121402(R) (2012)

Divacancies on Gr

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26x26 nm², +0.28V

- • Reconstructed « ⁵⁸⁵ » divacancies fromthe symmetry: 2 **pentagons**, 1 **octogon**.
- • Also from DFT simulated images (next slide).
- • The reconstruction suppresses the ^σ (sp2) DB in plane.

- \Box Spectra recorded on A and B divacancies show a broad resonance centered at +150 mV which present a rich internal structure mV, which present a rich internal structure.
- \Box Resonance is reproduced by DFT calculations, but not the fine internal structure \Box Spin polarized DET: non magnetic
- \Box Spin polarized DFT: non magnetic

Outline:

- Introduction to TMDs (mono or few layers).
- STM/STS on TMDs,
- Influence of the substrate,
- QPI measurements: role of the spin texture,
- Electronic structure of defects (point defects, twin boudaries, edges);
- \bullet In-plane heterojunctions.

Transition Metal Dichalcogénides (TMDs) : MX₂

A large (≈40) familly of 2D (lamellar) materials:

- Insulators
- **Semi-conductors**
- Métals (SC, CDW)

2H crystal structure of bulk materials.

2D TMD 2D: some devices…

- electrostatic doping using backgate
- transparent, flexible layers

Transistor built on ML MoS²

^μ > 200 cm²V-1 s-1 et **^ION/IOFF = 10⁸**

Radisavljevic Nature Nano 11

Ultrasensitive photodétector using ML MoS₂

Lopez-Sanchez Nature Nano 13

2D Heterostructures : LED with a hBN/Gr/WS₂ stack

EQE up to 10%

device electroluminescence

Withers Nature Mater. 15
TMDs as 2D semiconductors…

- • (Quasiparticle) Electronic bandgap measurement, exciton binding energy,
- •Scattering on defects: band structure and spin effects,
- •Defects in TMDs: edges, twin boudaries, X vacancies…
- **•** Heterojunctions: band alignment (out of plane and in plane). •

 M aterials: WX₂ and MoX₂.

1L: diffusion des quasiparticules

- • Determination of the VBM and CBM energies, consistency with ARPES for VB, Tip Induced Band Bending?
- •Exciton BE,
- •Role of the substrate,
- •Evolution with number of layers

Computed band structure for ML et BL MoSe² (**DFT**)

Yi Zhang et al., Nat. Nano 9, 111 (2014)

- •VBM at K point, spin-orbit split (180 meV),
- •VBM shifts to Γ point from 2 L,
- • Fair overall description of the band structure by DFT calculations.

•**CB??**

M. M. Ugeda, Nat. Mat. 13, 1091 (2014)

Assignment of the VB features from ARPES spectra on similar samples:

- •Strong ^Γ point features V2 and V3 (« long » decay lengths and no dispersion at Γ)
- •Weak V1 feature (« small » decay length in vacuum, more dispersive).

M. M. Ugeda, Nat. Mat. 13, 1091 (2014)

« Sophisticated » procedure for bandedges determination. A linear fit is used between $E_{CB, 2\sigma}$ and $E_{CB, 2\sigma}$ + ΔE , with ΔE≈0.15 V. Idem for VB.

Good S/N ratio and low T needed.

Figure S5. Bandgap determination. The bandgap of monolayer MoSe₂ was determined from the logarithm of 57 individual STS curves. One such curve is shown in purple. The logarithm of the mean of the signal within the bandgap is depicted in blue as $C_{g,av}$. The green line is two standard deviations above $C_{\text{g,av}}$. The red lines on either side of the curve are linear fit lines to the band edges. The gap edges are defined as the energies at which the linear fit lines cross $C_{g,av}$.

Tip Induced Band Bending (**TIBB**) results from poor screening of the electric field of the STS junctionnear the semiconductor surface.

- \bullet Well known for 3D systems (GaAs…), R. M. Feenstra PRB 50, 4561 (1994)
- • Depends on tip sample-distance, doping, surface states…
- **Increases the gap** (lowers the effective tip-surface •bias relative to the nominal one).

Variable current spectroscopy:

- •Set-point bias: +1.5V,
- Set-point current range 10 pA to 500 nA: variationof the tip-sample distance by 0.5 nm!
	- (can be measured through I(z) spectra).
- \bullet Shift of the V2 structure < 25 mV,
- \bullet Shift of the CB onset $≈ 0$ mV.
- \rightarrow **No** α **TIBB** α

Additionnal info: VBM structure V1 desappears at large tip-sample separation, as expected for a band located at K/-K

STS: electronic gap, single (quasi) particle gapCreation of independent electron and hole.

Optical gap: creation of a bound electron-hole pair (Coulombic interaction). *PL measurements give the exciton energy*

Exciton BE: STS gap- Optical gap.

For this system: **Exciton BE: 0.55±0.04 eV** Much larger than in 3D semiconductors (≈10 meV) M. Dvorak et al., PRL 110, 016402 (2013)

Evolution of band gap and exciton BE with alloying in MoxWi-xS2: A. F. Rigosi et al., PRB **94**, 075440 (2016)

M. M. Ugeda, Nat. Mat. 13, 1091 (2014)

On the **same ML MoSe² /BLG sample**: Optical gap: 1.63±0.01eV

- •• Shift of the FL relative to the band edges (discussed later).
- •Electronic gap is reduced by 11% on HOPG!
- •Exciton BE is reduced by 50%.
- •Consistent with better screening of the Coulomb interaction by HOPG.
- •(Same in $\frac{Q}{2}$ Zhang et al., 7:13843 (2016) for $\text{MoSe}_{2}/\text{hBN/Ru}$

Theory: The band gap and exciton binding energy decrease…. when a monolayer is surrounded by a high dielectric constant material *(such as graphene, and BN to a smaller extent)*. H-P. Komsa et al. PRB 86, 241201(R) (2012)

Adsoption of benzene/Graphite (weakly coupled system) J. B. Neaton et al., PRL 97, 216405 (2006)

Finally, the Coulomb interaction between theadded hole or electron associated with the ionization or affinity level will result in a polarization of the metal substrate. This additional correlation energy further stabilizes the added hole or electron, reducing the gap between affinity and ionization levels as illustrated (in Fig. 1) *above*.

A classical image potential model (1/4Iz-z₀I) **gives a good estimate of the amplitude ofthe effect** (obtained from GW calculations).

Semiconducting CNT on Au substrate (homogeneous $\phi \approx 1.4$ nm) H. Lin et al., Nat. Mat. 9, 235 (2010)

- •**Gap changes as a function of CNT/substrate distance,**
- •**Correctly described by a classical image potential.**

Band gap variation as a function of thickness. *The strong (relative) increase of the VB edge signal for >1 L indicates the shift of the VBM from K to Γ.*

- • Direct (at K)/indirect gap transition from 2 L, due to changes at Γ/Λ.
- • Related to the spatial distribution of the states (at K, Γ, Λ).

Charged defects in hBN. Dillon Wong et al., Nat. Nano. 10, 949 (2015)

Topo and **conductance** image à Vs=-0.4V (0.25nA) **Charge sign** of defects determined from additional STS data **p-n** junctions and electron confinement on these objects: J. Lee et al., Nat. Phys. 12, 1032 (2016).

Conductance image à Vs=-0.3V, variable Vg **The ring radius varies with Vg! Mechanism:** tip induced ionisation of the defect (close to the surface). On doped GaAs: K. Teichmann et al., PRL 101, 076103 (2008) **Local Lieu State Connect Local Connect Local tip gating**

Twin boundary defects in MBE grown MoSe₂ (on BLG/SiC(0001) or on HOPG)

STM image: -1.3V , 20pA, 4.5KMTB are the pairs of white lines.

nc-AFM image: atomic structure of the MTB. **Se** and **Mo** atoms.

A **dense array** of such « **1D metallic** » features can be obtained….STM image, 35x35 nm², -1.3V.

H. Liu et al., PRL 113, 066105 (2014)

S. Barja et al., Nat. Phys. 12, 751 (2016)

Inversion or Mirror **Twin Domain boundaries** (MoSe2 grains rotated by 180°).

The grain boundary generates an (almost) **metallic 1D « band » in the TMD gap**.

Possible CDW (x3a) distorsion → gap @ E^F

Extended defects #2: **edges.**

800x800nm², +1.0V

- • **Edges** (outlined in **green**) on a TMD flake are created by **breaking strong covalent** (TM-X) **in plane bonds**.
- In analogy with (2D) surfaces of (3D) crystals, the **high energy ideal structure** will **relax** following different strategies: atomic displacements, rebonding (reconstruction), passivation (change in chemical composition).
- • Some **« mid-gap »** (edge) **states** may remain within the TMD bandgap after relaxation which can impose (**pin**) **the Fermi level position at edges** (in analogy with 3D semiconductor surfaces).
- •**Band bending at edges will** (most likely) **result!**

•

Theory (DFT)

Computed band structure **with**or **without** edges.

> **First experimental evidence of edge states.**

1D Metallic edge state in MoS₂ nanoclusters grown on Au(111).
We're in the set of the second location M.V. Bollinger et al., PRL 87, 196803 (2001).

Extended defects #2: **edges. More evidence for edge states and band bending.**

Chendong Zhang et al., Nat. Comm. 7: 10349 (2016)

In-plane Heterojunctions (MBE or CVD growth)

CVD grown in-plane (1L) Heterojunction on SiO2/Si

630 nm

W atoms are brighter

Y. Gong et al., Nature Mat. 13, 1135 (2014). See also: C. Huang et al., Nature Mat. 13, 1096 (2014) for MoSe₂/WSe₂ in-plane junctions and M.-Y. Li et al. Science 349, 524 (2015) for WSe $_2$ -MoS $_2$ lateral p-n junction.

- • Heterojunctions are essential in 3D semiconductor electronics (HEMT, laser diodes…). *New physics can emerge in 2D semiconductor heterojunctions…*
- Similar atomic structure and lattice parameter allows for the growth of a coherent (seamless) •interface between MoX₂ and WX₂ (X=S, Se) with limited interdiffusion.
- •Enhanced PL intensity at the interface.
- •Intrinsic p-n (rectifying) lateral junction.
- •Band alignment at the interface?

In-plane Heterojunctions (MBE or CVD growth)

STS study of an in-plane $HJ : WS₂/Mo_{1-x}W_xS₂$ (x=0.3) grown on graphite.

Type II heterojunction,as expected.

High electric fieldat the interface $(8 10⁷ V/m)$ for efficient e-h separation.

S. Yoshida et al., Sci. Rep. 5, 14808 (2015)

